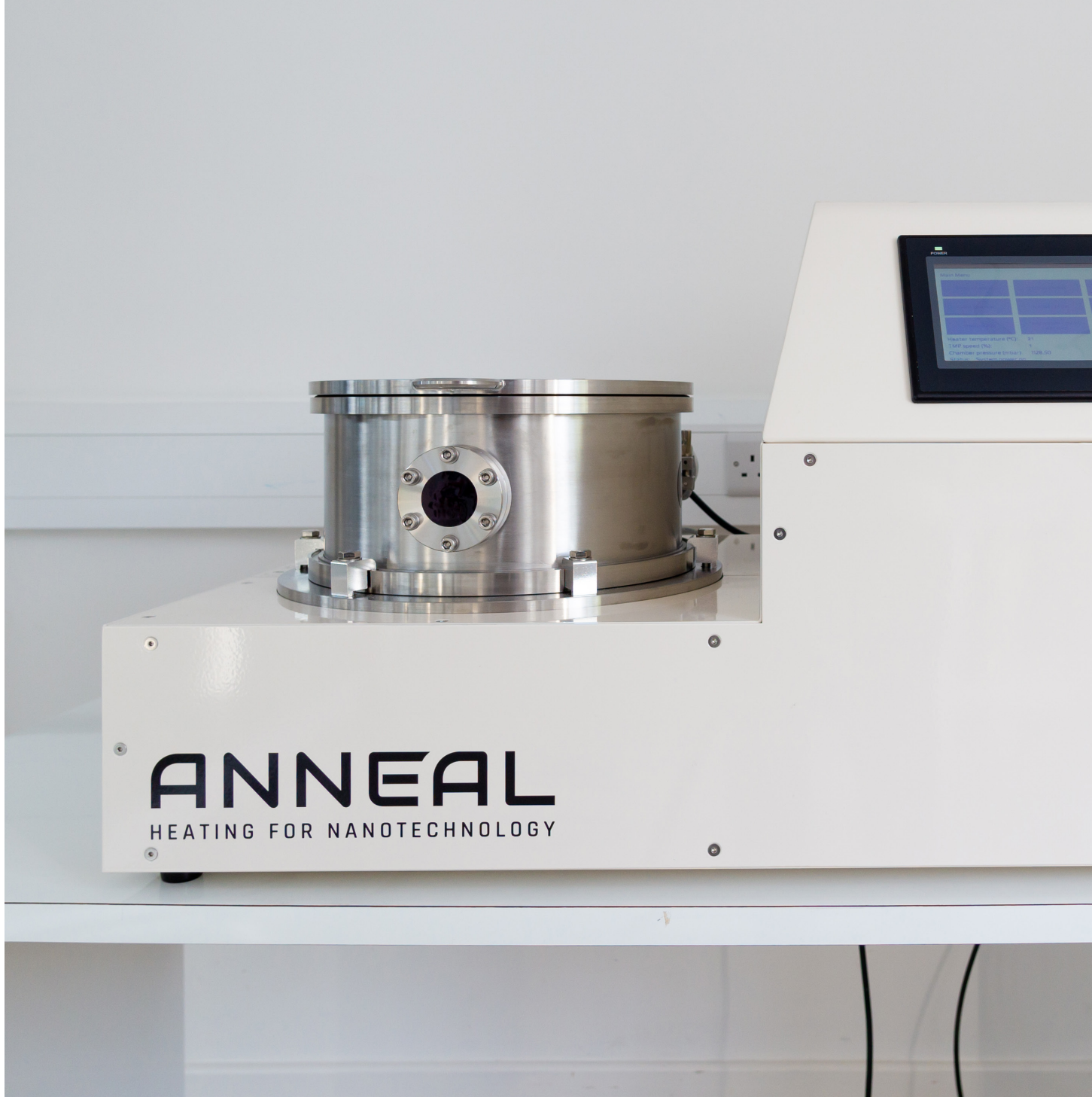
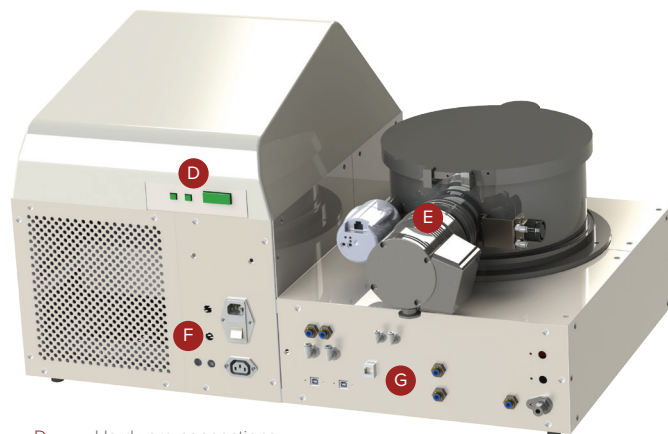


# ANNEAL by Moorfield.

High-temperature substrate processing up to 1000 °C.



A Vacuum chamber  
 B Chamber viewport  
 C HMI touchscreen

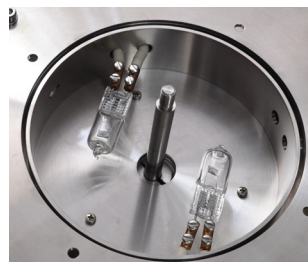
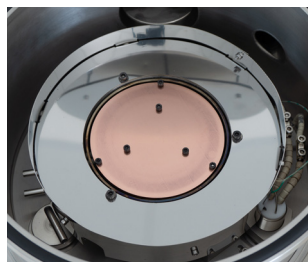


D Hardware connections  
 E Turbomolecular pump  
 F Electrical connections  
 G Service inlets/outlets panel

## ANNEAL systems from Moorfield are optimised for the thermal treatment of 2D materials and thin film devices under controlled atmospheres.

Substrates are supported face-up on stage-top platens that are situated centrally inside a stainless-steel high-vacuum chamber fitted with appropriate heat shielding and a shuttered viewport. Heating is via a heat source located beneath the platen. Maximum temperatures up to 1000 °C are possible—depending on the heating technology used.

- Up to 6" substrate diameters
- Stage temperatures up to 1000 °C
- Choice of heating technologies
- Typical heating rates of up to 0.3°C/s (500°C maximum temp.) and 8°C/s (1000°C maximum temp.)
- MFCs for process gas introduction
- Precise pressure control
- Turbomolecular/mechanical pumping systems
- Base pressures  $< 5 \times 10^{-7}$  mbar
- Easy sample access
- Easy operation via touchscreen HMI
- Define/save multiple process recipes
- Straightforward maintenance/servicing
- Comprehensive safety features
- Cleanroom compatible
- Proven performance



ABOVE: ANNEAL system  
 LEFT: Quartz lamp stage with water-cooled enclosure and extra thermocouple  
 CENTRE: Quartz lamp stage, platen removed  
 RIGHT: SiC element stage for 1000 °C substrate temperatures

Visit [moorfield.co.uk](http://moorfield.co.uk) or call +44(0) 1565 722609

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